Chapter 16. Atomic Layer Deposition for Biomimicry

Engineered Biomimicry

Edited by
Akhlesh Lakhtakia
Raúl J. Martín-Palma

Lianbing Zhang and

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With the development of new synthetic techniques and technological processes, the interest in biomimicry has gathered rejuvenation during the past decades. One particularly interesting research method may be the atomic level deposition (ALD), that was established in various areas of technology as a vacuum-based chemical-digesting technique and enabler for the deposition of extremely thin useful coatings. Subsequently, we summarize advancement in various study topics including ALD and biomimicry. In this chapter, brief descriptions of the technology and its own benefits and drawbacks are given. The benefits of this technology over equivalent techniques make it more and more attractive for applications in biomimicry.